



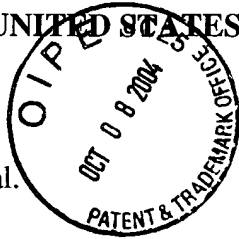
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Huey-Shin YUAN et al.

Serial No. 09/811,667

Filed: March 20, 2001



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Group Art Unit: 2163

Examiner:

For: FAULT TOLERANT AND AUTOMATED COMPUTER SOFTWARE WORKFLOW

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

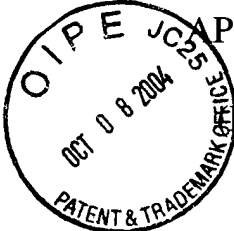
Wilmer Cutler Pickering Hale and Dorr LLP



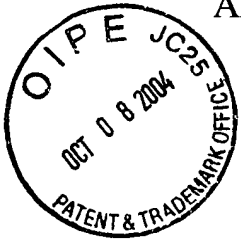
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<div>INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</div> <div></div>				ATTY. DOCKET NO. 005957 USA/ Consilium/Consilium		SERIAL NO. 09/811,667	
				APPLICANT Huey-Shin YUAN et al.			
				FILING DATE March 20, 2001		GROUP 2163	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	5,975,994	11/02/99	Sandhu et al.			06/11/97	
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	6,725,402 B1	04/20/04	Coss, Jr. et al.			07/31/00	
EXAMINER			DATE CONSIDERED				

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

<p style="text-align: center;">INFORMATION DISCLOSURE CITATION IN AN APPLICATION</p> <p style="text-align: center;">(PTO-1449)</p> 	<p>ATTY. DOCKET NO. 005957 USA/ Consilium/Consilium</p>	<p>SERIAL NO. 09/811,667</p>
	<p>APPLICANT Huey-Shin YUAN et al.</p>	
	<p>FILING DATE March 20, 2001</p>	<p>GROUP 2163</p>
<p style="text-align: center;">OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</p>		
	<p>IslamRaja, M. M., C. Chang, J. P. McVittie, M. A. Cappelli, and K. C. Saraswat. May/June 1993. "Two Precursor Model for Low-Pressure Chemical Vapor Deposition of Silicon Dioxide from Tetraethylorthosilicate." <i>J. Vac. Sci. Technol. B</i>, Vol. 11, No. 3, pp. 720-726.</p>	
	<p>Kim, Eui Jung and William N. Gill. July 1994. "Analytical Model for Chemical Vapor Deposition of SiO₂ Films Using Tetraethoxysilane and Ozone" (Abstract). <i>Journal of Crystal Growth</i>, Vol. 140, Issues 3-4, pp. 315-326.</p>	
	<p>Guo, R.S, A. Chen, C.L. Tseng, I.K. Fong, A. Yang, C.L. Lee, C.H. Wu, S. Lin, S.J. Huang, Y.C. Lee, S.G. Chang, and M.Y. Lee. June 16-17, 1998. "A Real-Time Equipment Monitoring and Fault Detection System." <i>Semiconductor Manufacturing Technology Workshop</i>, pp. 111-121.</p>	
	<p>Lantz, Mikkel. 1999. "Equipment and APC Integration at AMD with Workstream." <i>IEEE</i>, pp. 325-327.</p>	
	<p>July 15, 2004. Office Action for U.S. Serial No. 10/172,977, filed June 18, 2002.</p>	
	<p>August 2, 2004. Office Action for U.S. Serial No. 10/174,377, filed June 18, 2002.</p>	
	<p>August 9, 2004. Written Opinion for PCT Serial No. PCT/US02/19063.</p>	
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	<p>September 9, 2004. Written Opinion for PCT Serial No. PCT/US02/21942.</p>	
	<p>September 16, 2004. International Preliminary Examination Report for PCT Serial No. PCT/US02/24859.</p>	
EXAMINER	DATE CONSIDERED	

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